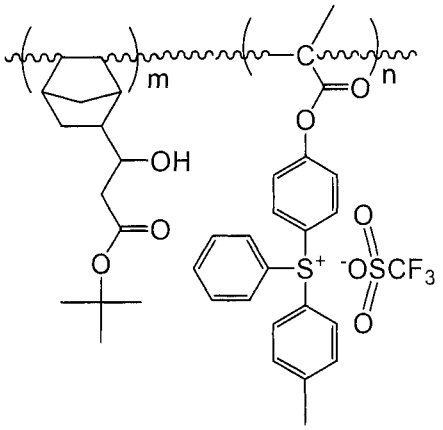
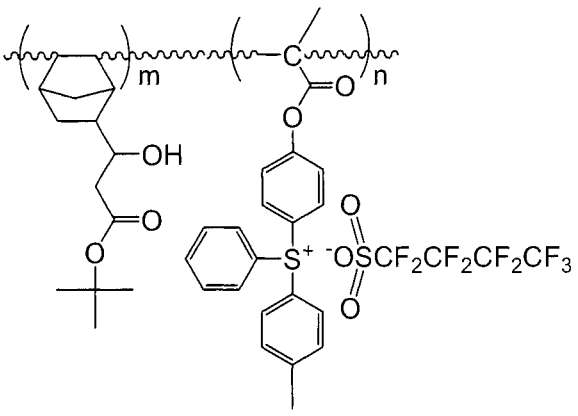
WHAT IS CLAIMED IS:

1. A resist composition comprising a hydrophilic photoacid generator, a base copolymer and a solvent, wherein the photoacid generator is selected from the group consisting of compounds represented by Formulae 18 to 20:

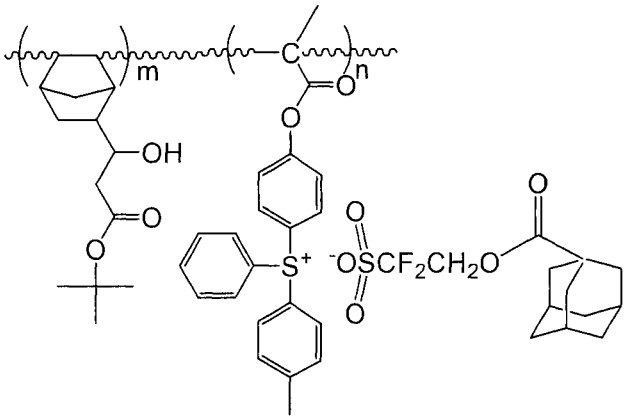
[Formula 18]



[Formula 19]



[Formula 20]



wherein, in Formulae 18 to 20, Ph represents a phenyl group, and m and n are numbers of repeat units present in the main chain and satisfy m+n=1, $0<m/(m+n)\leq 0.99$ and $0<n/(m+n)\leq 0.99$.

2. The resist composition according to claim 1, wherein the hydrophilic photoacid generator has a weight average molecular weight in terms of polystyrene measured by gel permeation chromatography (GPC) of 1,000 to 500,000 g/mol.

3. The resist composition according to claim 1, wherein the hydrophilic photoacid generator has a ratio of weight average molecular weight to number average molecular weight of 1 to 5.

4. The resist composition according to claim 1, wherein the hydrophilic photoacid generator is present in an

amount of 0.3 to 10 parts by weight, with respect to 100 parts by weight of a solid content of the resist composition.